	Application No.	Applicant(s)
Notice of Allemet '''	09/836,884	DENIS ET AL
Notice of Allowability	Examiner	DENIS ET AL. Art Unit
	Khiem D Nguyen	0000
		2823
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiativ of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.		
1. This communication is responsive to <u>03/04/04</u> .		, m
2. ☑ The allowed claim(s) is/are 1-25.		
3. The drawings filed on <u>17 April 2001</u> are accepted by the Ex		
4. Acknowledgment is made of a claim for foreign priority und	aminer.	
a) ☐ All b) ☐ Some* c) ☐ None of the:	•	
1. Certified copies of the priority documents have	been received.	
2. Certified copies of the priority documents have	been received in Application No.	
Copies of the certified copies of the priority doc	uments have been received in this	national stage application from th
International Bureau (PCT Rule 17.2(a)).		Tallerial stage application from th
* Certified copies not received:	**	
5. Acknowledgment is made of a claim for domestic priority un	der 35 U.S.C. § 119(e) (to a provisi	onal application)
(a) The translation of the foreign language provisional application has been received.		
6. Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.		
Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application. THIS THREE-MONTH PERIOD IS NOT EXTENDABLE 7. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.		
THE CHARLE PATEINT APPLICATION (PTO-152) Which gives reason	n(s) why the oath or declaration is	deficient.
8. CORRECTED DRAWINGS must be submitted.		
(a) ☐ including changes required by the Notice of Draftsperso	on's Patent Drawing Review (PTO-	948) attached
1) ∐ hereto or 2) ☐ to Paper No.		
(b) ☐ including changes required by the proposed drawing co	prrection filed which has be	en approved by the Evernines
(c) ☐ including changes required by the attached Examiner's	Amendment / Comment or in the C	of approved by the Examiner.
Identifying indicia such as the application number (see 37 CFR 1.8 each sheet.	4(c)) should be written on the drawing	gs in the front (not the back) of
DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.		
Attachment(s)		
☑ Notice of References Cited (PTO-892)	-	
Notice of Preferences Cited (PTO-892) Notice of Draftperson's Patent Drawing Review (PTO-948) Information Disclosure Statements (PTO-1449), Paper No. 030	4☐ Interview Summa	Patent Application (PTO-152) ry (PTO-413), Paper No
☐ Examiner's Comment Regarding Requirement for Deposit		dment/Comment
of Biological Material	ø∐ Examiner's Staten 9∐ Other	ment of Reasons for Allowance
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Application/Control Number: 09/836,884

Art Unit: 2823

DETAILED ACTION

Allowable Subject Matter

Claims 1-25 are allowed.

Reasons For Allowance

The following is a statement of reasons for the indication of allowable subject matter. The prior art taken alone or in combination neither discloses nor makes obvious the instant process of claims as a whole. Specifically, the prior art of record, Noguchi (U.S. Patent 6,461,901) discloses a process for forming at least one transistor on a substrate 100, the process comprises depositing on the substrate at least one layer of semiconductor material 104 wherein the substrate is made of a quartz glass but fails to teach or suggest the Applicant's steps of a process for forming at least one transistor on a substrate, which process comprises depositing on the substrate at least one layer of semiconductor material, wherein the substrate comprises a polyphenylene polyimide as as recited in the currently amended independent claim 1, lines 1-3. The secondary reference Derwent Abstract (JP 63084089) teaches a substrate comprising a layer of polyphenylene polyimide similar to the preferred substrate used in the present invention. However, the Abstract only teach that this substrate is useful as a substrate for formation of flexible printed circuits and does not teach that this substrate is useful for the formation of film transistors thereon.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably

Art Unit: 2823

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accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Khiem D Nguyen whose telephone number is (571) 272-1865. The examiner can normally be reached on Monday-Friday (8:00 AM - 5:00 PM).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on (571) 272-1855. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 305-3432 for regular communications and (703) 305-3432 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

K.N. May 13, 2004

W. DAVID COLEMAN PRIMARY EXAMINER